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(71) Applicant *(for all designated States except US)*: **ASML HOLDING N.V.** [NL/NL]; De Run 6501, NL-5504 DR Veldhoven (NL).

(72) Inventors; and

(75) Inventors/Applicants *(for US only)*: **FARNSWORTH, Windy, Lynn** [US/US]; 10 Pheasant Lane, New Milford, CT 06776 (US). **DEL PUERTO, Santiago** [US/US]; 14 Lillie Lane, Milton, NY 12547 (US). **NAYFEH, Samir A.** [US/US]; 18 Faulkner Road, Shrewsbury, MA 01545 (US).

(74) Agents: **LEEMING, John Gerard** et al.; J.A. Kemp & Co., 14 South Square, Gray's Inn, London WC1R 5JJ (GB).

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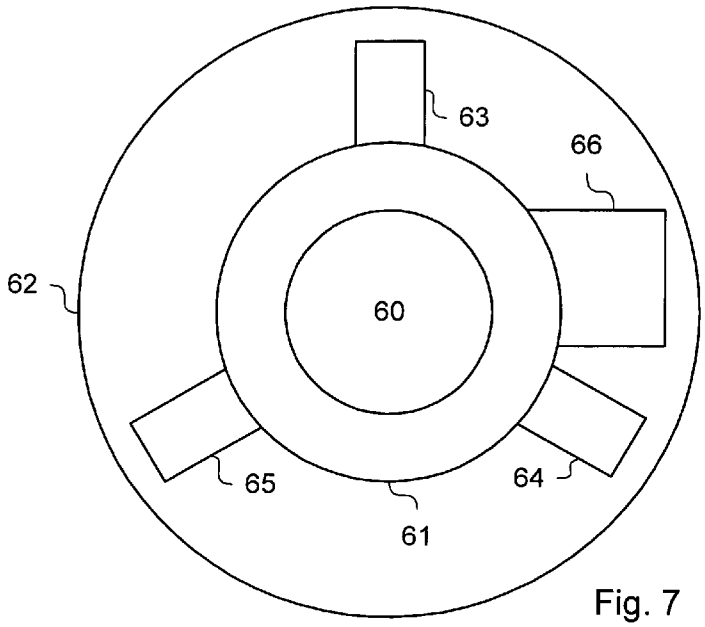

Fig. 7

(57) Abstract: In a lithographic apparatus, dampers (63, 64, 65) are provided that may be used within mounts for optical elements (60) in order to damp the motion of the optical element relative to the component to which it is mounted.

WO 2009/062606 A1